



U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

Information Disclosure
Statement

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GROUP:

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date
MK	6,015,761	01/18/00	Merry	438/727	438/723	6/26/96
MK	6,055,927	05/02/00	Shang	118/723MI	118/723E	1/14/97
MK	4,867,841	9/19/89	Loewenstein	156/643	156/646	5/27/88

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

Publication: Patent Cooperation Treaty (PCT)
Translation: English
Document Number: 03077786 Date: 4/10/91 ✓
Country: Japan
Class Or Subclass C23C 16/44
Patent: Yes _ No X
Title: Film Forming Device Provided with Deposit Recovering Device

Publication: Patent Cooperation Treaty (PCT)
Translation: English
Document Number: 0429 809 A2 Date: 10/10/90 ✓
Country: Germany
Class Or Subclass H01L 21/00
Patent: Yes _ No X
Title: Method and Apparatus for Etching Semiconductor Materials

Publication: Patent Cooperation Treaty (PCT)
Translation: English
Document Number: WO 99/02754 Date: 1/21/99 ✓
Country: Greate Britain
Class Or Subclass C23C 16/44
Patent: Yes _ No X
Title: Remote Plasma Celaning Apparatus

OTHER DOCUMENTS (Including Author, Title, Place of Date, Publication)

Examiner

Date Considered

12/10/02

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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